

ADVANCES IN CHEMISTRY SERIES **221**

Microelectronics Processing

Chemical Engineering Aspects

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CONTENTS

Preface	xiii
1. Microelectronics Processing	1
Dennis W. Hess and Klavs F. Jensen	
2. Theory of Transport Processes in Semiconductor Crystal Growth from the Melt	35
Robert A. Brown	
3. Liquid-Phase Epitaxy and Phase Diagrams of Compound Semiconductors	105
Timothy J. Anderson	
4. Physical Vapor Deposition Reactors	171
T. W. Fraser Russell, Bill N. Baron, Scott C. Jackson, and Richard E. Rocheleau	
5. Chemical Vapor Deposition	199
Klavs F. Jensen	
6. Diffusion and Oxidation of Silicon	265
Richard B. Fair	
7. Resists in Microlithography	325
Michael J. O'Brien and David S. Soane	
8. Plasma-Enhanced Etching and Deposition	377
Dennis W. Hess and David B. Graves	
9. Interconnection and Packaging of High-Performance Integrated Circuits	441
Ronald J. Jensen	
10. Semiconductor Processing Problems Solved by Wet (Solution) Chemistry	505
Marjorie K. Balazs	

INDEXES

Author Index	523
Affiliation Index	523
Subject Index	523